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Docket No. N1085-00018 Inventors: Chung-Hsing Chang et al. "Clear Field Annular Type Phase Shifting Mask" Sheet 1 of 9

100

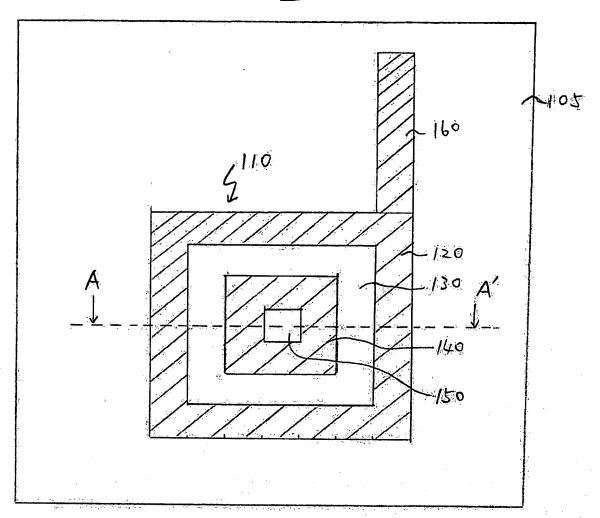


FIG 1A

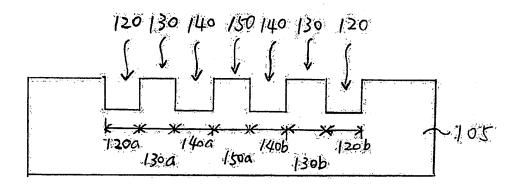


FIG. 1B

200

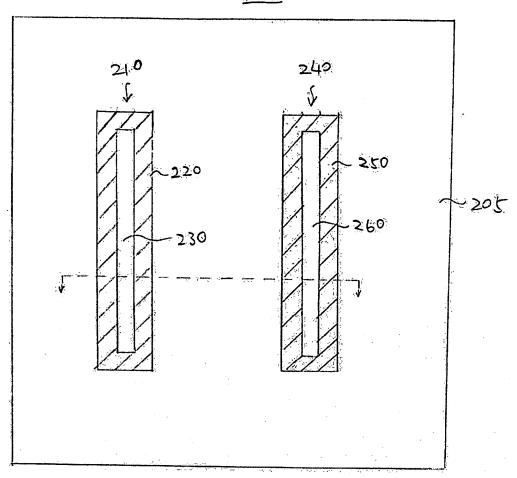


FIG ZA

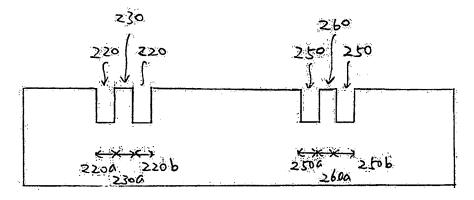


FIG 2B

FIG. 3A

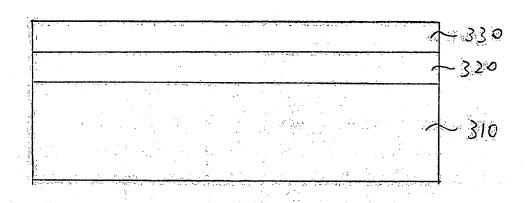
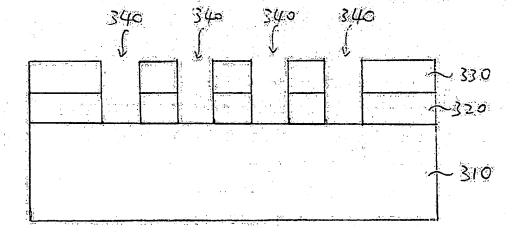


FIG 3B



F14, 3C

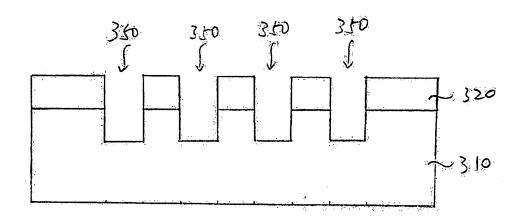


FIG 3D

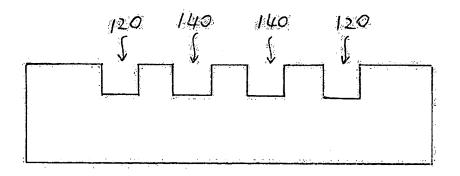


FIG 3E

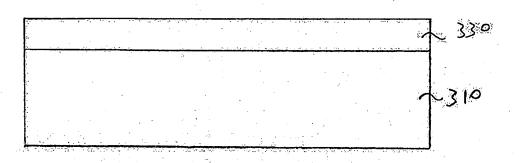
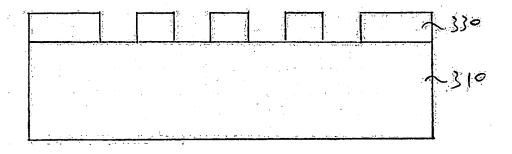
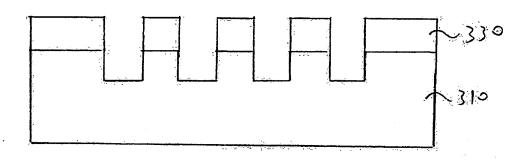


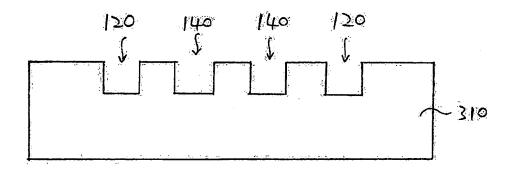
FIG 3F

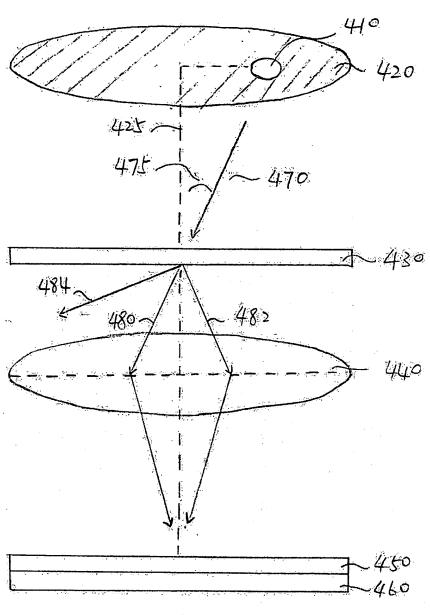


F16. 3G



F14. 3H





F16.4

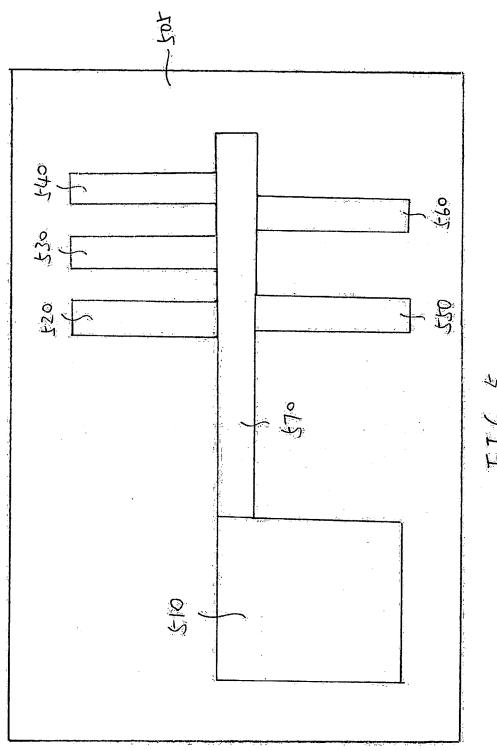


FIG. S

